

(b) Amendments to the Specification

Page 1, after line 1, please substitute the Title of the Invention with the following replacement Title:

~~--MESOSTRUCTURED THIN FILM MESOPOROUS THIN FILM,
AND PROCESS FOR PRODUCTION THEREOF~~

PROCESS OF FORMING A UNIAXIALLY ORIENTED
MESOTRUCTURED FILM ON A UNIAXIALLY ORIENTED
POLYMER COMPOUND--

Please substitute the paragraph beginning at page 10, line 27 and ending at page 11, line 12, with the following replacement paragraph:

--Fig 2 is an explanatory drawing of an example of the reactor for forming a silica mesostructured thin film of the present invention. The material consisting of the reactor 21 is not specially limited, provided that the material is resistant against chemicals, especially acids, including polypropylene and polyfluoroethylene (commercial name: ~~Teflon~~ TEFLON). As shown in fig. 2, for example, an acid-resistant substrate holder 23 is placed in the reactor 21 to hold a substrate 25. A lid 22 made of ~~Teflon~~ TEFLON or a like material seals the reactor with a seal 24 like an O-ring. In Fig. 2, the substrate 25 is held horizontally, but is not limited thereto.--